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To All Concerned

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Representative:
(Securities code: 6235 Tokyo Stock Exchange, 1st Section)
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Completion of ALD Coating System

We are pleased to announce new ALD (Atomic Layer Deposition) Coating System is ready for sale, enabling more advanced coating applications which helps our customers to provide various and more sophisticated products in addition to already selling ones in precision optics. We integrated the ALD technology prepared by Afly solution Oy (Finland), acquired by us lately, with our company's plasma technology to develop a new plasma atomic layer deposition system (A800P) optimized for thin film coating, and development has now been completed.

The feature of this new system is its ability to perform uniform, ultrathin and low-temperature coating formation on curved surfaces of lenses, and complex surfaces of 3D structures, etc. In addition, the plasma atomic layer deposition system can perform mass coating that was a challenge for such a technology. It also contributes to improve customer's production efficiency by optimizing raw material supplies and plasma exposure to shorten coating time. This system is expected to be utilized to coat antireflection films on sophisticated camera lenses installed in smartphones and protection films for lithium-ion batteries/micro LEDs, etc.

Going forward, we will continue to make efforts to apply new film deposition technologies in new systems which enables us to develop new markets.

Reference:

The Atomic Layer Deposition (ALD) method is a film deposition technology developed in Republic of Finland that utilizes vacuum nature and is a method in which atoms are deposited one layer at a time utilizing the self regulating characteristics of atoms.